## High-performance broadband phototransistor array of PdSe<sub>2</sub>/SOI Schottky junction

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Fig. S1 Optical image of the fabricated PdSe<sub>2</sub>/Si phototransistor.



Fig. S2 UPS spectra of PdSe<sub>2</sub> film. The calculation formula of Fermi energy level of PdSe<sub>2</sub> is as

follows:  $E_F = 21.22 \ eV - 15.98 \ eV = 5.24 \ eV$ .



**Fig. S3** Noise spectral density versus frequency for PdSe<sub>2</sub>/Si phototransistor at gate voltages of 0 V and 5 V.



Fig. S4 Time-dependent photocurrent of  $PdSe_2/Si$  phototransistor under 1550 nm illumination at  $V_G$ = 0 V and  $V_{DS}$  = 0 V.



**Fig. S5** Photoresponse characteristics of PdSe<sub>2</sub>/Si phototransistor to pulsed light irradiation at frequencies of (a) 1 kHz, (b) 5 kHz, (c) 10 kHz and (d) 15 kHz under 808 nm illumination. (e) Rising and falling edges for estimating the rise time ( $\tau_r$ ) and the fall time ( $\tau_f$ ) of PdSe<sub>2</sub>/Si phototransistor at pulsed light frequency of 5 kHz under 808 nm illumination ( $V_G = 0$  V and  $V_{DS} = 0$  V). (f) Frequency response characteristic of PdSe<sub>2</sub>/Si phototransistor.